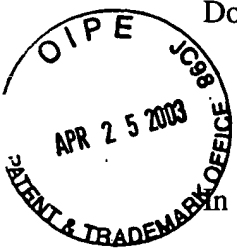


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5-20-83

Docket No.: 005198 USA/Consilium/Consilium

PATENT/OFFICIAL



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Parris C.M. HAWKINS et al.

Serial No. 09/800,980

Filed: March 8, 2001

For: DYNAMIC AND EXTENSIBLE TASK GUIDE

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Group Art Unit: 2121

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SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents
Washington, D.C. 20231

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

This submission does not constitute a representation that a search has been made or that no better art exists and does not constitute an admission or representation that any of the listed documents is material or constitutes prior art. If it should be determined that any of the listed documents does not constitute prior art under the United States law, Applicants reserve the right

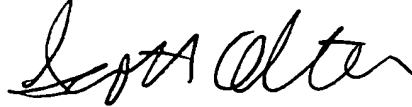
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to present to the Office the relevant facts and law regarding the appropriate status of such document.

No certification or fee is believed to be required. However, the Commissioner is hereby authorized to charge any additional fees should any be required for this submission, or credit any overpayment to deposit account no. 08-0219.

Respectfully submitted,

HALE AND DORR LLP

A handwritten signature in black ink, appearing to read "Scott M. Alter", written over a horizontal line.

Scott M. Alter

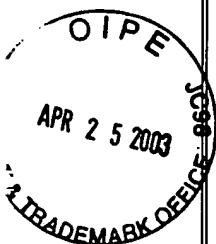
Registration No. 32,879

1455 Pennsylvania Avenue, NW
Washington, DC 20004

TEL 202.942.8428 SMA/lrm

FAX 202.942.8484

Date: 4/25/03



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	6,517,413	02/11/03	Hu et al.			10/25/00

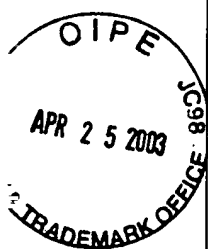
FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
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	61-66104	04/04/86	Japan			X	
	3-202710	09/04/91	Japan			X	
	8-23166	01/23/96	Japan			X	
	9-246547	09/19/97	Japan			X	
	WO 98/05066	02/05/98	WIPO			X	
	10-34522	02/10/98	Japan			X	
	0 869 652	10/07/98	Europe			X	
	WO 99/09371	02/25/99	WIPO			X	
	0 910 123	04/21/99	Europe			X	
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	WO 00/00874	01/06/00	WIPO			X	
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	'WO 01/18623	03/15/01	WIPO			X	
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	'434103	05/16/01	Taiwan			X	
	'436383	05/28/01	Taiwan			X	
	'455938	09/21/01	Taiwan			X	
	'455976	09/21/01	Taiwan			X	
	'2001-284299	10/12/01	Japan			X	
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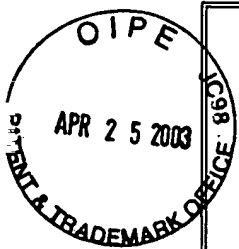
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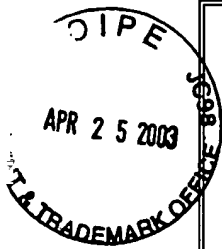
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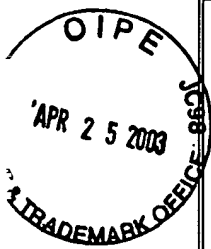
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